

Highlights

 Various surface textures available such as grooved, embossed, plain, and perforated Soft pad, vertical pore structure on compressible substrate

POLITEXTM

POLITEXTM (sometimes referred to as POLITEXTM Supreme), was originally developed for final wafer polishing. It is manufactured from proprietary polyurethane and incorporates a unique, vertically oriented pore structure with a compressible substrate. The substrate is designed to instantaneously recover from polishing compression, creating a pumping action that enhances slurry flow within the pad to produce optimum surface finish quality. This attribute reduces pad loading and increases pad life, which is well suited for final polishing of silicon, oxide, glass, or metals.

Typical applications

Aluminum, beryllium, cadmium, zinc telluride, calcium fluoride, ceramic, fused silica, glass, indium phosphide, lithium niobate, lithium tantalate, nickel, polysilicon, silicon, tungsten, zerodur

Polishing pad	Base material	Compressibility [%]	Thickness [mils]
POLITEX™ Reg	Poromeric	14.75	56
POLITEX™ Hi	Poromeric	13.75	60
POLITEX™ Reg Embossed	Poromeric	14.75	56

The data presented is a statistical representation for comparison purposes. The values are not necessarily representative of the COA specifications.

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PUREON



Politex pad performance is optimized when using in combination with an ULTRA-SOL™ slurry product.



Pureon offers a variety of slurries in a wide range of viscosities and custom formulations to match POLITEX™ pads. We are happy to assist you in finding the best suitable products.



Pureon offers a wide range of customized solutions. Get in touch with us.

Product specifications

Base material Poromeric
Shelf life 12 months

Application recommendations

Handling

Apply only to a clean, dry surface at room temperature. If an appropriate solvent, such as isopropyl alcohol, is used to clean the platen after a pad removal, allow the platen to dry completely and return to room temperature before applying a new pad. Solvents remaining on the platen or an unusually cold platen will lower PSA adhesion.

When applying the pad to the platen, peel the release liner from one edge of the pad. Fold liner back approximately two inches. Align the pad with the edge of the platen and adhere. In one continuous movement, slowly peel the remaining release liner off the pad while pressing the pad down on the platen. The application should be smooth and uniform with even pressure from the pad mounting tool (such as a flat disk or hand roller).

Do not try to reposition pads with PSA adhesive.

Storage

Product should be stored and transported in the original packaging. The product should be stored in temperatures between 10 °C to 24 °C (50 °F to 75 °F) and < 50 % humidity. Exposure for six (6) months or less to conditions between -17 °C to 48 °C (0 °F and 120 °F) and / or at relative humidity of up to 100 % will not impact the product performance as long as the release liner remains intact and attached to the PSA. If the product is exposed to temperatures and humidity outside the recommended conditions, it may still be acceptable for use. In all cases, the product should be allowed to return to normal room temperatures prior to use.

Disposal

Dispose of in accordance with all applicable local regulations.

 ${\tt POLITEX^{TM}}\ is\ a\ registered\ trademark\ of\ DuPont.\ Pureon\ is\ an\ authorized\ distributor\ for\ DuPont.$

